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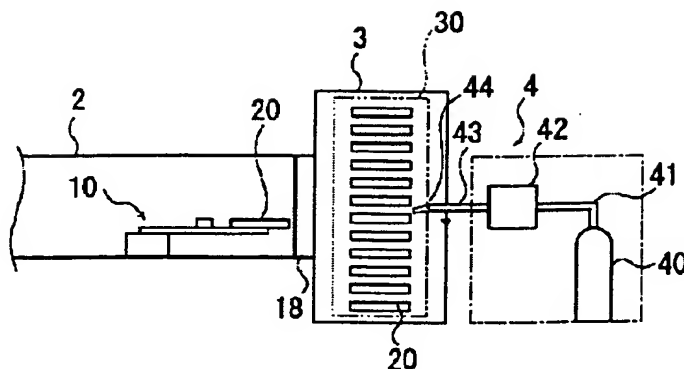
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TITLE : SUBSTRATE DISCHARGING METHOD,
SUBSTRATE DISCHARGING DEVICE
AND VACUUM TREATMENT DEVICE



ABSTRACT : PROBLEM TO BE SOLVED: To provide a technique for stably and repeatedly electrostatically attracting a substrate at the time of performing treatment in a vacuum.

SOLUTION: This substrate discharging method for removing electric charges remaining in the substrate 20 in a vacuum comprises a process of removing the electric charges of the substrate 20 by leading an ionized gas for neutralization to the surface of the substrate 20 housed in an airtight cassette chamber 3. The gas for the discharging generated in a substrate discharging device 4 outside the cassette chamber 3 is introduced into the cassette chamber 3, and gas for the discharging is blown from the tip of a nozzle 44 to the surface of the substrate 20. Consequently, even when electrostatic attraction is repeated, the residual electric charges are not accumulated in the substrate 20.

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